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S3	1	(716/19).ccls. and (wafer adj simulation) and (threshold adj data)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/07 11:14
S4	0	(716/21).ccls. and (wafer adj simulation) and (threshold adj data)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/07 11:14
S5	0	(716/21).ccls. and (wafer adj simulation) and (threshold same (resist adj model))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/07 11:14
S6	2	(716/19).ccls. and (wafer adj simulation) and (threshold same (resist adj model))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/07 11:14

S7	2	("716"/$).ccls. and (wafer adj simulation) and (threshold same (resist adj model))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/07 11:15
S8	3	(wafer adj simulation) and (threshold same (resist adj model))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/07 11:16
S9	39	(wafer and simulation) and (threshold same (resist adj model))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/07 13:38
S10	3	(wafer and simulation) and (threshold same (resist adj model)) and ((look-up adj table) or LUT)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/07 13:07

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12-14 Sept. 2000 Page(s):96 - 102
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